EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	863	703/6.ccls.	US-PGPUB; USPAT; EPO; DERWENT	OR	OFF	2007/02/27 16:25

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L1	46	local adj flare	US-PGPUB; USPAT; EPO; DERWENT	OR	OFF	2007/02/27 17:15
L2	4	("20030068565" | "20040021854" | "20040196447" | "6233056").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2007/02/27 17:32
L3	4573	flar$3 and mask	US-PGPUB; USPAT; EPO; DERWENT	OR	OFF	2007/02/27 17:33
L4	1367	L3 and (lithography or photolithography)	US-PGPUB; USPAT; EPO; DERWENT	OR	OFF	2007/02/27 17:35
L6	364	L4 and (OPC or correction)	US-PGPUB; USPAT; EPO; DERWENT	OR	OFF	2007/02/27 17:52
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R Hynes

K Nandra

E Gotthelf

E Robinson

L Ericsson

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Effectiveness and confirmation of local area flare measurement method in various pattern layouts - group of 3 »
D Nam, E Lee, S Jung, YS Kang, G Yeo, J Lee, H Cho ... - Proc. SPIE, 2002 - spie.org
... The LOAFER is designed to measure the local area flare of the lens, that is, the
short and mid-range flare and the **local flare** distribution of the exposure ...
Cited by 4 - Related Articles - Cached - Web Search

Development of 157-nm full-field scanners - group of 3 »
H Hata, H Nogawa, S Suda - Proceedings of SPIE, 2004 - link.aip.org
... When compared to ArF, **local flare** increases significantly. However, it has
been confirmed that **local flare** can be greatly mitigated ...
Cited by 3 - Related Articles - Web Search

Local flare effects and correction in ArF lithography - group of 2 »
T Yao, M Osawa, T Minami, N Yamamoto, H Aoyama, G ... - VLSI Technology, 2003. Digest of Technical
Papers. 2003 ..., 2003 - ieeexplore.ieee.org
Page 1. 4B-1 **Local Flare** Effects and Correction in ArF Lithography Teruyoshi Yao,
Morimi Osawa, Takayoshi Mind , Norihiro Yamamoto, Hajime Aoyama, Genshi Okuda, ...
Cited by 1 - Related Articles - Web Search

Unsteady Aerodynamics of an Ablating Flared Body of Revolution Including Effect of Entropy Gradient - group of 2 »
LE Ericsson - AZAA Journal, 1968 - pdf.aiaa.org
... **local flare** forces become dynamically destabilizing. ... 2 and the **local "flare
efficiency"** type of effects can easily be compted . It ...
Cited by 8 - Related Articles - Web Search

Correction for local flare effects approximated with double Gaussian profile in ArF lithography - group of 4 »
M Osawa, T Yao, H Aoyama, K Ogino, H Hoshino, Y ... - Journal of Vacuum Science & Technology B:
Microelectronics ..., 2003 - link.aip.org
... been developed for correcting line width variations due to midrange flare with a
scattering range of over a few tens of micrometers (which we call **local flare** ...
Cited by 1 - Related Articles - Web Search - BL Direct

Application of Realistic Model Atmospheres to Eclipse Maps of Accretion Disks: The Effective ... - group of 3 »
EL Robinson, JH Wood, RA Wade - The Astrophysical Journal, 1999 - journals.uchicago.edu
... 4 1 at the outer edge, giving h/r r . This latter relation yields a slope of
dh/dr 0.1 at the outer edge of the disk, corresponding to a **local flare** angle of ...
Cited by 9 - Related Articles - Web Search - BL Direct

The Properties of the Relativistic Iron K-Line in NGC 3516 - group of 7 »
K Nandra, IM George, RF Mushotzky, TJ Turner, T ... - The Astrophysical Journal, 1999 -
journals.uchicago.edu
... the variation in the blue wing could be due to an enhancement in the illuminating
flux of the inner disk portion moving toward us, due to a **local flare** (cf. ...
Cited by 117 - Related Articles - Web Search - BL Direct

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F Murai

H Yoda

Y Zheng

M Osawa

S Okazaki

Fast proximity effect correction method using a pattern **area density** map - group of 4 »

F **Murai**, H Yoda, S Okazaki, N Saitou, Y Sakitani - Journal of Vacuum Science & Technology B:
Microelectronics ..., 1992 - link.aip.org
... using a pattern **area density** map. [Journal of Vacuum Science & Technology B:
Microelectronics and Nanometer Structures 10, 3072 (1992)]. Fumio **Murai**, Haruo Yoda ...
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Proximity effect correction using pattern shape modification and **area density** map for electron-beam ... - group of 4 »

M Osawa, K Takahashi, M Sato, H Arimoto, K Ogino, ... - Journal of Vacuum Science & Technology B:
Microelectronics ..., 2001 - link.aip.org
Proximity effect correction using pattern shape modification and **area density**
map for electron-beam projection lithography. [Journal ...
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Pattern fabrication method using a charged particle beam and apparatus for realizing same - group of 5 »

H Yoda, F **Murai** - US Patent 5,278,421, 1994 - Google Patents
... A CHARGED PARTICLE BEAM AND APPARATUS FOR REALIZING SAME [75] Inventors: Haruo Yoda;
Fumio **Murai**, both of ... posed is extremely small and that the **area density** ...
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Greater number of microtubules per axon of unmyelinated fibers of mutant quails deficient in ... - group of 3 »

... , M Mizutani, T Yamamoto, H Hayashi, Y **Murai** - Acta Neuropathologica, 1994 - Springer
... JX Zhao - A. Ohnishi () 9 T. Yamamoto 9 Y. **Murai** Department of Neurolog); University
of ... NF per axon and per m 2 of the transverse axonal **area (density)** were cal ...
Cited by 6 - Related Articles - Web Search - BL Direct

Variation in bone mineral density of the sacrum in young adults and its significance for sacral ... - group of 4 »

Y Zheng, WW Lu, Q Zhu, L Qin, S Zhong, JC Leong - Spine, 2000 - spinejournal.com
... calculated from quantitative computed tomography (QCT), was used to obtain **area**
density (g/cm ... Okuyama K, Sato K, Abe E, Inaba H, Shimada Y, **Murai** H. Stability ...
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K Takahashi, M Osawa, M Sato, H Arimoto, K Ogino, ... - Journal of Vacuum Science & Technology B:
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... F. **Murai**, H. Yoda, S. Okazaki, N. Saitou, and Y. Sakitani, "Fast proximity effect
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Proximity-effect correction for EPL by using multiple pattern-**area**- **density** maps and pattern ... - group of 5 »

F **Murai**, H Fukuda, S Mori, A Sato, K Nakajo - Proceedings of SPIE, 2003 - spie.org
Abstract. PUBLICATIONS. Proximity-effect correction for EPL by using multiple
pattern-**area**- **density** maps and pattern classification **Murai**, Fumio, Hitachi, Ltd. ...
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Yao, T.; Osawa, M.; Minami, T.; Yamamoto, N.; Aoyama, H.; Okuda, G.; Sawano, T.; Kamatsuki, I.; Sugimoto, F.;
Futatsuya, H.; Kobayashi, K.; Ogino, K.; Hoshino, H.; Machida, Y.; Arimoto, H.; Asai, S.;
VLSI Technology, 2003. Digest of Technical Papers. 2003 Symposium on
10-12 June 2003 Page(s):43 - 44

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☐ 2. **Forward and Backward Scattered Modes in Multimode Nonuniform Transitions**
Tang, C.C.H.;
Microwave Theory and Techniques, IEEE Transactions on
Volume 16, Issue 8, Aug 1968 Page(s):494 - 502

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☐ 3. **Test structure for fixing OPC of 200 nm pitch via chain using inner and outer dummy via array**
Nasuno, T.; Matsubara, Y.; Minami, A.; Uchida, N.; Kobayashi, H.; Aoyama, H.; Tsuda, H.; Tsujita, K.; Wakamiya, W.;
Kobayashi, N.;
Microelectronic Test Structures, 2004. Proceedings. ICMTS '04. The International Conference on
22-25 March 2004 Page(s):23 - 28

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☐ 4. **Intense electron beam propagation by charge neutralization from a dielectric collimator**
Vijayan, T.; Roychowdhury, P.; Iyyengar, S.K.;
Plasma Science, IEEE Transactions on
Volume 22, Issue 2, April 1994 Page(s):199 - 204
Digital Object Identifier 10.1109/27.279023

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☐ 5. **2003 Symposium on VLSI Technology. Digest of Technical Papers (IEEE Cat. No.03CH37407)**
VLSI Technology, 2003. Digest of Technical Papers. 2003 Symposium on
10-12 June 2003

AbstractPlus | Full Text: PDF(461 KB)   IEEE CNF
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☐ 6. **"SIG-NABOUT"-the development and trial of a novel junction design**
Webb, P.J.;
Road Traffic Monitoring and Control, 1994., Seventh International Conference on
26-28 Apr 1994 Page(s):106 - 110

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A Erdmann

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G Dulk

Model-based OPC/DRC considering local flare effects - group of 3 »
H Futatsuya, T Yao, M Osawa, K Ogino, H Hoshino, H ... - Proceedings of SPIE, 2004 - link.aip.org
... including local **flare** effects, and its results. The **simulation** results show good
agreement with the experimental results, indicating that effective **OPC**/DRC ...
Web Search

New process models for OPC at sub-90-nm nodes - group of 6 »
Y Granik, NB Cobb - Proceedings of SPIE, 2003 - perso.enst-bretagne.fr
... Optical **flare** CMPnon- uniformity Illuminator optics ... Outside of the modeling range,
the target bias **OPC** will be used PRINTimage **simulation** contours Figure 10. ...
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Relevance of TCAD to process-aware design - group of 6 »
VK Singh, J Garcia-Colevatti - Proceedings of the SPIE, 2002 - uos.ac.kr
... Impact of aberrations on design – Layout dependent **flare** in EUV ... **simulation** Page 20.
TCAD ... models to build/strengthen **OPC** models Complexity Run time Aerial ...
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Relevance of technology computer aided design (TCAD) to process-aware design
V Singh, J Garcia-Colevatti - Journal of Microlithography, Microfabrication, and ..., 2002 - link.aip.org
... with one of the areas within TCAD, lithography **simulation**. ... In addition to **OPC** and
the short-range effects ... such effects are lens aberrations and **flare**, with the ...
Related Articles - Web Search - BL Direct

Transistor flaring in deep submicron-design considerations - group of 5 »
V Singhal, CB Keshav, KG Sumanth, PR Suresh - Design Automation Conference, 2002. Proceedings
of ASP-DAC ..., 2002 - ieeexplore.ieee.org
... 4.1 Designing out **flares**- A solution for high ... Our analysis with statistical **simulation**
results showed that we ... Most **OPC** based corrective schemes, which involve ...
Related Articles - Web Search

Limits of strong phase-shift patterning for device research - group of 7 »
M Fritze, RD Mallen, B Wheeler, D Yost, JP Snyder, ... - Proceedings of SPIE, 2003 - photronics.com
... test cells, no clear influence of long range **flare** ... Fig 6: IC Workbench aerial image
simulation of transistor gate with and without **OPC** described in ...
Cited by 3 - Related Articles - View as HTML - Web Search

Propagation and absorption of electron-cyclotron maser radiation during solar flares - group of 4 »
ME McKean, RM Winglee, GA Dulk - Solar Physics, 1989 - Springer
... could provide the heating necessary to explain some soft X-ray features observed
in solar **flares**. ... 0 = 90 , opc/12 e = 0.3, oph/2 e = 0.03, and Ls = 105 km. ...
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Potential issues on optical proximity correction (OPQ) using double dipole lithography
TB Chiou, S Hsu, M Eurlings, E Hendrickx, A Chen - Microprocesses and Nanotechnology Conference,
2004. Digest ..., 2004 - ieeexplore.ieee.org
... to describe the short- and mid-range **flare** as a ... be used as an input parameter in
the lithography **simulator**. ... is able to improve the accuracy of **OPC** calibration. ...
Related Articles - Web Search

Comparison of simulation approaches for chemically amplified resists - group of 5 »
A Erdmann, W Henke, S Robertson, E Richter, B ... - Proc. SPIE, 2001 - sigma-c.de

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<u>R Winglee</u>

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<u>Correction for local **flare** effects approximated with double Gaussian profile in ArF lithography - group of 4 »</u>
M Osawa, T Yao, H Aoyama, K Ogino, H Hoshino, Y ... - Journal of Vacuum Science & Technology B: Microelectronics ..., 2003 - link.aip.org
... to local **flare** intensity and is independent of pattern layout considering the order of the local **flare** correction (LFC) and optical proximity correction (**OPC**). ...
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<u>Model-based **OPC**/DRC considering local **flare** effects - group of 3 »</u>
H Futatsuya, T Yao, M Osawa, K Ogino, H Hoshino, H ... - Proceedings of SPIE, 2004 - link.aip.org
... **OPC**/DRC using this method is possible. Model-based **OPC**/DRC considering local **flare** effects. [Proceedings of SPIE 5377, 451 (2004)]. ...
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[CITATION] Model-based **OPC**/DRC considering local **flare** effects [5377-40]
H Futatsuya, T Yao, M Osawa, K Ogino, H Hoshino, H ... - PROCEEDINGS-SPIE THE INTERNATIONAL SOCIETY FOR OPTICAL ..., 2004 - International Society for Optical Engineering; 1999
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<u>Investigation of stray light characteristic by multiple Gaussian modeling and its **OPC** application - group of 3 »</u>
HC Kim, DS Nam, GS Yeo, SJ Lee, SG Woo, HK Cho, WS ... - Proceedings of SPIE, 2004 - link.aip.org
... scattering range characteristic of **flare**. To minimize CD errors from **OPC**, **flare** level and EOR should be considered in the **OPC** procedure. ...
<u>Web Search</u>

<u>Relevance of TCAD to process-aware design - group of 6 »</u>
VK Singh, J Garcia-Colevatti - Proceedings of the SPIE, 2002 - uos.ac.kr
... ò Focus on aspects of Lithography – Design coupling – Some challenges in **OPC** – Impact of aberrations on design – Layout dependent **flare** in EUV ...
<u>Cited by 1</u> - <u>Related Articles</u> - <u>View as HTML</u> - <u>Web Search</u>

<u>... of techniques to measure the point spread function due to scatter and **flare** in EUV lithography ... - group of 4 »</u>
M Chandhok, SH Lee, CG Krautschik, G Zhang, BJ ... - Proceedings of SPIE, 2004 - spie.org
... expected that to meet the CD control requirements for the 32 nm node, **Flare** Variation Compensation (FVC), akin to Optical Proximity Correction (**OPC**) would be ...
<u>Cited by 4</u> - <u>Related Articles</u> - <u>Cached</u> - <u>Web Search</u>

<u>Test structure for fixing **OPC** of 200 nm pitch via chain using inner and outer dummy via array - group of 2 »</u>
T Nasuno, Y Matsubara, A Minami, N Uchida, H ... - Microelectronic Test Structures, 2004. Proceedings. ICMTS'04 ..., 2004 - ieeexplore.ieee.org
... width and length of dummy patterns are shrunk drastically by OPE and local **flare** effect, However, inner pattern can be protected. In the case of **OPC** A, length ...
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<u>New process models for **OPC** at sub-90-nm nodes - group of 6 »</u>
Y Granik, NB Cobb - Proceedings of SPIE, 2003 - perso.enst-bretagne.fr
... hard because the **flare** has long interaction range, which results in the destruction of the design hierarchy and consequential explosion of **OPC** runtime. ...
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<u>Correction for local **flare** effects approximated with double Gaussian profile in ArF lithography - group of 4 »</u>
M Osawa, T Yao, H Aoyama, K Ogino, H Hoshino, Y ... - Journal of Vacuum Science & Technology B: Microelectronics ..., 2003 - link.aip.org
... The CD variation due to local **flare** was reduced from 22 ... GB of memory each) were used to **calculate** each process ... processing times are much faster than the **OPC** ones ...
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<u>Propagation and absorption of electron-cyclotron maser radiation during solar flares - group of 4 »</u>
ME McKean, RM Winglee, GA Dulk - Solar Physics, 1989 - Springer
... to explain some soft X-ray features observed in solar **flares**. ... 0 = 90 , **opc**/12 e = 0.3, oph/2 e = 0.03 ... Plotted are: Equation (11) (solid line) and numeri- cal ...
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<u>Relevance of TCAD to process-aware design - group of 6 »</u>
VK Singh, J Garcia-Colevatti - Proceedings of the SPIE, 2002 - uos.ac.kr
... ò Focus on aspects of Lithography – Design coupling – Some challenges in **OPC** – Impact of aberrations on design – Layout dependent **flare** in EUV ...
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<u>Orientation dependent shielding for use with dipole illumination techniques</u>
DFUSUS HSU, NUS CORCORAN, JFUS CHEN - EP Patent 1,385,052, 2004 - freepatentsonline.com
... and horizontal mask patterns and application of **OPC** techniques as ... The percentage of **flare** was calculated using the following equation: Straylight % = E0 ...
<u>Cached</u> - <u>Web Search</u>

<u>High numerical aperture lithographic imagery at the Brewster angle</u>
TA Brunner, N Seong, WD Hinsberg, JA Hoffnagle, FA ... - Journal of Microlithography, Microfabrication, and ..., 2002 - link.aip.org
... by the pupil edge, defocus effects, image **flare** effects, stage ... mask will need more accurate **calculation** than that ... for optical proximity correction (**OPC**) methods ...
<u>Cited by 7</u> - <u>Related Articles</u> - <u>Web Search</u> - <u>BL Direct</u>

<u>The low-level radial velocity variability in Barnard's star (= GJ 699) - group of 5 »</u>
M Kürster, M Endl, F Rouesnel, S Els, A Kaufer, S ... - A&A, 2003 - aanda.org
... For all data used in our **calculation** (Hip = Hipparcos, Nid = Nidever et al. ... H index (middle spectrum offset by 0.5 flux units), and the **flare** event (upper ...
<u>Cited by 22</u> - <u>Related Articles</u> - <u>Cached</u> - <u>Web Search</u> - <u>BL Direct</u>

<u>The low-level radial velocity variability in Barnard's star (= GJ 699) - group of 6 »</u>
M Kurster, M Endl, F Rouesnel, S Els, A Kaufer, S ... - A&A, 2003 - edpsciences.org
... For all data used in our **calculation** (Hip = Hipparcos, Nid = Nidever et al. ... H α index (middle spectrum offset by 0.5 flux units), and the **flare** event (upper ...
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<u>Enhancements in rigorous simulation of light diffraction from phase-shift masks - group of 4 »</u>
A Erdmann, N Kachwala - Proc. SPIE, 2002 - sigma-c.de
... thin masks there is no necessity to perform a new **calculation** of the ... This occurs for subresolution features on optical proximity corrected (**OPC**) masks, for ...
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Nasuno, T.; Matsubara, Y.; Minami, A.; Uchida, N.; Kobayashi, H.; Aoyama, H.; Tsuda, H.; Tsujita, K.; Wakamiya, W.; Kobayashi, N.;
Microelectronic Test Structures, 2004. Proceedings. ICMTS '04. The International Conference on
22-25 March 2004 Page(s):23 - 28

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☐ **2. Transistor flaring in deep submicron-design considerations**
Singhal, V.; Keshav, C.B.; Sumanth, K.G.; Suresh, P.R.;
Design Automation Conference, 2002. Proceedings of ASP-DAC 2002. 7th Asia and South Pacific and the 15th International Conference on VLSI Design. Proceedings.
7-11 Jan. 2002 Page(s):299 - 304
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☐ **3. FPGA as Process Monitor-an effective method to characterize poly gate CD variation and its impact on product performance and yield**
Xiao-Yu Li; Feng Wang; La, T.; Zhi-Min Ling;
Semiconductor Manufacturing, IEEE Transactions on
Volume 17, Issue 3, Aug. 2004 Page(s):267 - 272
Digital Object Identifier 10.1109/TSM.2004.831934

AbstractPlus | References | Full Text: PDF(1080 KB)   IEEE JNL
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☐ **4. A redundancy method of AS traffic in signaling gateway using loadsharing scheme**
Hyunjeong Lee; Byungsun Lee;
Advanced Communication Technology, 2004. The 6th International Conference on
Volume 2, 2004 Page(s):833 - 837
Digital Object Identifier 10.1109/ICACT.2004.1292986

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☐ **5. An effective method of characterization poly gate CD variation and its impact on product performance and yield**
Xiao-Yu Li; Feng Wang; Tho La; Zhi-Min Ling; Ji-Fu Kung; Wang, M.H.; Horng Nan Chem; Chia-Pin Lee;
Semiconductor Manufacturing, 2003 IEEE International Symposium on
30 Sept.-2 Oct. 2003 Page(s):259 - 262

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☐ **6. A pattern matching system for linking TCAD and EDA**
Gennari, F.E.; Neureuther, A.R.;
Quality Electronic Design, 2004. Proceedings. 5th International Symposium on

SPIE—The International Society for Optical Engineering

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